

FORM PTO-1449 (MODIFIED)		ATTORNEY DOCKET NO.	SERIAL NO.
LIST OF PATENTS AND PUBLICATIONS		SP01-331	10/086,231
O FOR APPLICANTS INFORMATION DISCLOSURE STATEMENT		APPLICANT Bowden et al.	
		FILING DATE February 27, 2002	GROUP:



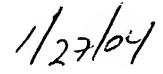
REFERENCE DESIGNATION

U.S. PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Name	Class	Sub-Class	Filing Date if Approp.
IN	AA	2,326,058	8/3/43	Nordberg	100	52	RECEIVED JUN 28 2002
CL	AB	4,501,602	2/26/85	Miller et al.	65	18.2	100
CL	AC	5,043,002	8/27/91	Dobbins et al.	65	3.12	100
CL	AD	5,152,819	10/6/92	Blackwell et al.	65	212	100
CL	AE	5,154,744	10/13/92	Blackwell et al.	65	312	100
CL	AF	5,686,728	11/11/97	Shafer	250	492.2	100
CL	AG	5,970,751	10/26/99	Maxon et al.	65	414	100
CL	AH	6,013,399	1/11/00	Nguyen	430	5	100
CL	AI	6,299,318	10/9/01	Braat	359	856	

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Sub-Class	Translation Yes No
CL	AJ	WO 01/07967	2/1/01	PCT	G03C	5/00	X
CL	AK	WO 01/08163	2/1/01	PCT	G21K	5/00	X
CL	AL	WO 01/75522	10/11/01	PCT	G03F	1/14	X
CL	AM	WO 00/48775	8/24/00	PCT	B23B		X
IN	AN	WO 02/32622	4/25/02	PCT	B24B	7/24	X
IN	AO	WO 02/26647	4/4/02	PCT	C03B	37/016	X
CL	AP	WO 02/32616	4/25/02	PCT	B23P	13/04	
CL	AQ	EP 0 903 605A2	3/24/99	EPO	G02B	13/14	X
CL	AR	EP 1 106 582A2	6/13/01	EPO	C03B	19/10	X

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OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)

PL	A1	P. Shultz & H. Smith, Ultra-Low-Expansion Glasses and Their Structure in the SiO ₂ -TiO ₂ System, Amorphous Materials, papers presented to the Third International Conference on the Physics of Non-Crystalline Solids, held at Sheffield University, September 1970
CL	A2	George H. Beall, Industrial Applications of Silica, Reviews in Mineralogy, Vol. 29 (Silica), (1994), 469-505.
CL	A3	Charles Gwyn et al., Extreme Ultraviolet Lithography, November 1999, 97-141.
CL	A4	EUV Lithography NGL Technology Review, June 9, 1999, Chicago, Illinois
CL	A5	Charles Gwyn et al., Extreme Ultraviolet Lithography, 1-6.
CL	A6	William M. Tong et al., Substrates Requirements For Extreme Ultraviolet Lithography, Information Science & Technology, Lawrence Livermore National Laboratory, December 1999.
CL	A7	O.V. Mazurin et al., Crystallization of Silica and Titanium Oxide-Silica Corning Glasses (Codes 7940 & 7971), Journal of Non-Crystalline Solids 18, (1975) 1-9.
CL	A8	ISIMOTO CO. LTD., Purity and Chemical Reactivity, http://www.isimoto.com/isimoto/english/feature1.html , 1-3, 5/17/99
CL	A9	ISIMOTO CO. LTD., Product Information, http://www.isimoto.com/isimoto/english/product_info.html , 1-4, 5/17/99
CL	A10	Rapid Prototyping, http://mtiac.iitri.org/pubs/rp/rp1.htm
PL	A11	Products: SLS (R) Systems – Introduction, Vanguard TM and Vanguard TM HS, http://www.3dsystems.com/products/slsystems/vanguard/index.asp?promo=1
CL	A12	Corning, Semiconductor Materials ULE Zero Expansion Glass, http://www.corning.com/semiconductormaterials/products_services/ule.asp
CL	A13	Richard H. Stulen et al., Extreme Ultraviolet Lithography, IEEE Journal of Quantum Electronics, Vol. 35, No. 5, May 1999, 694-699..

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